ABSTRACT OF THE DISCLOSURE

A nitride compound semiconductor element having improved characteristics, productivity and yield. A nitride compound semiconductor element includes: a sapphire substrate; a first single crystalline layer of AlN formed on said sapphire substrate; a second single crystalline layer formed on said first single crystalline layer, said second single crystalline layer being made of $Al_xGa_{1-x}N$ (0.8 $\leq x \leq$ 0.97) and having a thickness of equal to or more than 0.3 μ m and equal to or less than 6 μ m; and a device structure section of a nitride semiconductor formed on said second single crystalline layer.